

## **Nano silver oxide based on insulator for optoelectronic device**

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### **ABSTRACT**

The high quality, high transparent conductive nano and micro silver oxide ( $\text{Ag}_2\text{O}$ ) films were successfully deposited quartz substrate as substrates using the pulsed laser reactive deposition (RPLD) method. The optical results tests showed high transparency values reached to (90) % and these results found of a sharply reduction with the low values of fluency of laser. The values of the optical band gap of the prepared films at the optimum value of the preparation condition is about 3.65eV, the surface morphology give a uniform structure with the average roughness of (1.61 nm).